

FORM PTO - 1449

INFORMATION DISCLOSURE STATEMENT

ATTORNEY DOCKET NO.: ASC-001C1

APPLICANT(S): Hammond et al.

SERIAL NO.: 10/688,003

FILING DATE: October 17, 2003

GROUP: Not yet assigned 28//

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	All	6,448,840	09/10/2002	Kao et al.			_		
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SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

ATTORNEY DOCKET NO.: ASC-001C1

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A43 6,593,191 07/15/2003 Fitzgerald		A41	6,555,839	04/29/2003	Fitzgerald			257	19		
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SUPPLEMENTAL INFORMATION			APPLICANT(S): Hammond et al.				
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